# Development of Optical Systems for Hard X-rays at SPringe 8 Yoshio Suzuki JASRI/SPring-8 

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## Development of Hard X-ray Optics at SPring-8

1. Beamline configurations,
2. Fresnel zone plate optics

Micro- \& nano-beam generation and characterization,
Imaging microscopy and tomography applications,
Holography and phase-contrast imaging,
Use of quasi-monochromatic (direct undulator) radiation,
3. Total reflection mirror optics,
4. Sputtered-sliced zone plate optics,
5. Refractive lens optics,
6. Theory of resolution limit.

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BL08W High Energy Inelastic Scattering


O BL08B2 Hyogo BM Hyogo Prefecture

* BL09XU Nuclear Resonant Scattering
* BL10XU High Pressure Research


## nce II

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BL11XU JAERI Materials Science II

- BL12XU NSRRC ID
$\qquad$ National Synchrotron Aadiation Research Center
+ 

BL13XU Surface and Interface Structures,

- BL14B1 JAERI Materials Science IBL15XU WEBRAM National Institute for Materials Science
- BL16XU Industrial Consortium ID Industrial Consortium
- BL16B2 Industrial Consortium BM Industrial Consortium
$\diamond$ BL17SU RIKEN Coherent Soft X-ray Spectroscopy.- BL19LXU RIKEN SR Physics

大
RI19R2 Engineering.Science Besearch
H BL20XU Medical and Imaging II

* BL20B2 Medical and Imaging I

BL22XU JAERI Actinide ScIence

- BL23SU JAERI Actinide Science I
- BL24XU Hyogo ID

RIKEN Coherent X-ray Optics BL29XU Hyogo Pretecture

+ BL25SU Soft X-ray Spectroscopy of Solid
BL26B1 RIKEN Structural Genomics I

BL: Beamline
B1, B2: Bending Magnets
XU: X-ray Undulator
SU: Soft X-ray Undulator
W: Wiggler
WEBRAM: Wide Energy range Beamline for Research in Advanced Materials NSRRC: National Synchrotron Radiation Research Center

IR: Infrared Radiation
LEP: Laser-Electron Photon LXU: Long-length Undulator SS: Straight Section

$\bigcirc \diamond \square:$ Planned or Under construction


April 1, 2004

BL20XU (Coherent optics, Microbeam, Holography, Interferometer, etc.) Undulator, Medium Length ( $\mathbf{2 4 8} \mathbf{~ m}$ ) beamline.
BL20B2 (Computer Tomography, Topography, Medical Imaging, etc.) Bending Magnet, Medium Length ( 215 m).
BL37XU (Fluorescent X-ray Micro-analysis) Undulator, Normal Length ( $\mathbf{5 0} \mathbf{m}$ ) beamline.
BL47XU (Microbeam, Imaging Microscopy \& Micro-CT) Undulator, Normal Length $(\mathbf{5 0} \mathbf{m})$ beamline.
(BL28B2: BM white beam, topography, BL29XU: RIKEN, 1 km BL)
Energy range:
5-113 keV,
Spatial Coherence:
$\sim 1 \mathrm{~mm}$ @ $1 \AA$ (BL20XU),
Beam Cross-section:
$\sim \mathbf{3 0} \mathrm{nm}$ (micro-focus) - $\mathbf{3 0 0} \mathbf{~ m m}$ ( $\mathbf{2 1 5} \mathbf{~ m}$-beamline with BM source).
Flux Density:
$\sim 10 \mathrm{E} 14$ photons $/ \mathrm{s} / \mathrm{mm} 2$ (direct beam),
$>10 \mathrm{E} 11$ photons $/ \mathrm{s} / \mu \mathrm{m} 2$ (micro-focus).



## 248 m-long Beamline, BL20XU, at SPring-8



Experimental setup
Application of Coherent X-ray Beam
-X-ray In-line Holography -


Measured Point-spread-function
"Zooming Tube"
Hamamatsu Photonics C5333
Photo-cathode: CsI (~2000£),
Magnification: 5-240,
Resolution (point-spread-function): $\mathbf{0 . 7} \boldsymbol{\mu} \mathrm{m}$ in FWHM.


EX-ray Energy: 8 keV


X-ray Energy: 80 keV

Object: Gold Wire, $50 \mu \mathrm{~m}$ Diameter, Imaging Detector: Zooming Tube, C5333, Hamamatsu Photonics, Field of View: $300 \mu \mathrm{~m}$ in Diameter.

Measured Hologram of Test Object

## Measurement of X-ray Coherence using Two-beam Interferometer with Prism Optics



Schematic diagram of experimental setup at beamline 20XU of SPring-8

Possible Applications

1. Two-beam Holography,
2. Phase Measurement,
3. Quantitative Measurement of Spatial Coherence,
4. Wavelength Filter, Harmonics Selection .

$$
\begin{aligned}
& \Delta \theta=\delta / \tan \theta, \\
& \delta=1.35 \times 10{ }^{-6} \rho \lambda^{2} .
\end{aligned}
$$

$$
\begin{aligned}
& \Delta \theta=2 \mu \mathrm{rad} \\
& \text { for } \rho=1.2, \lambda=1 \AA, \theta=45^{\circ} . \\
& \Delta \theta=46 \mu \mathrm{rad} \\
& \text { for } \theta=2^{\circ}
\end{aligned}
$$

Optical system for two-beam interferometer with X-ray prism.


Typical interference fringe patterns measured at an X-ray wavelength of 1 A. Beam deflection angle: $\Delta \theta=44 \mu \mathrm{rad}$.
Slit dimensions: $18 \mu \mathrm{mx} 19 \mu \mathrm{~m}$.
Measured fringe spacing is $2.3 \mu \mathrm{~m}$.
Beam overlap is $300 \mu \mathrm{~m}$. Exposure time is $\mathbf{6 0} \mathrm{s}$.

(a) $1.5 \AA$ and 3 degrees

(b) $1.0 \AA$ and 2 degrees

(c) $0.5 \AA$ and 1 degree

## Interference Fringes measured with X-ray Zooming Tube.

Prism to detector distance: $\mathbf{6 . 9} \mathbf{m}$, Field of view : $100 \mu \mathrm{~m}$ in diameter, X-ray wavelength: $0.5,1.0$, and $1.5 \AA$, Glancing angle to prism surface: $1.0,2.0$, and 3.0 degrees.

Cu grid mesh $64 \mu \mathrm{~m}$ pitch


Test Patterns $5 \mu \mathrm{~m} \mathrm{~L} / \mathrm{S}$


Hologram


Reconstructed Image

Leith-Upatnieks Type Two-beam Holography $\lambda=1.0 \AA$, Sample to image detector: 6.7 m


Visibility of interference fringes.
Solid squares, circles and triangles represent experimental data, Solid line, dotted line and dashed line are respective theoretical curves for source size of $100 \mu \mathrm{~m}, 50 \mu \mathrm{~m}$, and $20 \mu \mathrm{~m}$.

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3. Total reflection mirror optics,
4. Sputtered-sliced zone plate optics,
5. Refractive lens optics,
6. Theory of resolution limit.


## Experimental Setup of X-ray Microbeam/Scanning Microscopy at BL20XU

Diameter: $150 \mu \mathrm{~m}$, Designed focal Length: 100 mm at 8 keV , Outermost zone width $\left(d_{\mathrm{N}}\right): 0.1 \mu \mathrm{~m}$.

Diffraction limit $\left(=1.22 d_{N}\right): 0.12 \mu \mathrm{~m}$, numerical aperture: $7.5 \times 10^{-4}$ at 8 keV , Zone material: Ta, $1 \mu$ m-thick, Supporting membrane: $\mathrm{Si}_{3} \mathrm{~N}_{4}$, or $\mathrm{SiC}, 2 \mu$ m-thick. Fabrication method: electron-beam lithography technique at NTT-AT
$\mathrm{Si}_{3} \mathrm{~N}_{4}$ membrane ( $2 \mu \mathrm{~m}$-thick)


Schematic Drawing of Zone Plate Structure


Focused Beam Profile Measured by Knife-edge Scan
FZP: Ta $1 \mu$ m-thick,
Outermost Zone Width: $0.1 \boldsymbol{\mu m}$, EB-lithography at NTT-AT, Focal Length: 100 mm @ 8 keV .


Diffraction Efficiency of Ta-FZP
Closed Circle: Experimental Results, Solid Line: Calculated Efficiency assuming the Thickness of $1 \mu \mathrm{~m}$.

Total flux of microbeam: $\mathbf{1 0}^{\mathbf{9}}$ photons/s, Focused beam size: $0.12 \mu \mathrm{~m}$.

Bright-field: Transmitting beam through edge
Dark-field: Scattered beam at the edge


## Dark-field Knife-edge Scan Method for Focus Test

Primary beam (direct beam) is cut off with an aperture in front of X-ray detector. The scattered X-rays are selected by the aperture.

## Advantages of dark-field method:

1. Thin and phase object as knife-edge,
2. No differential processing,
3. Precise measurement.

- Result of Numerical Simulation


Assumed Cross-section of Knife-edge. Tapered edge with width of $b$, and phase shift of $\phi \mathbf{0}$.


Result of Numerical Simulation


## Result of Knife-edge Test

 Bright-field and Dark-field methodOutermost Zone Width: 50 nm, 1st-order Focus, $f=80 \mathrm{~mm}$ @ 8 keV , Knife-edge: gold wire of $50 \mu \mathrm{~m}$ diameter.

Dark Field


## 70 nm line \& Space




- Measured Value

Theory
$1 \mu \mathrm{~m}$

$76 \times 163$ pixels, $12.5 \mathrm{~nm} /$ pixel, Dwell Time: 0.5 s .
Scanning Microscopy
Test Patterns (Ta 500 nm-thick), X-ray Energy: 8 keV .


Kohzu Seiki, type YA-05-14.
Stepping Motor, Oriental Motor PX535MH-B.
Motor Driver, Melec, micro-step drive H-583.
Position Monitor, KEYENCE LC2420.


## Test Result of Linear Translation Stage

Kohzu Seiki, type YA-05-14.
Stepping Motor, Oriental Motor PX535MH-B.
Motor Driver, Melec, micro-step drive H-583.
Position Monitor, KEYENCE LC2420.

## Lifetime of Ta-FZP for radiation damage

$\sim 3$ days in air,
>> 1 month in vacuum or in He.


Irradiation in air


FZP: $100 \mu \mathrm{~m}$ diameter, $0.25 \mu \mathrm{~m}$ outermost zone width, X-ray energy: $10 \mathrm{keV} @ B L 47 X U$, Flux density: $\sim 5 \times 10^{13}$ photons $/ \mathrm{s} / \mathrm{mm}$, Total flux: $\sim 10^{17}$ photons

Damage problem is solved at present!


Schematic Diagram Experimental Setup for Imaging Microscopy and Micro-tomography
@ BL47XU


Imaging Microscopy
Objective \&Sample:FZP with $0.25 \mu \mathrm{~m}$ outermost zone width, X-ray Energy: 8 keV .


- Coherent Illumination -

- Incoherent Illumination-


## Imaging Microscopy with FZP Objective

- Effect of Beam Diffuser -

X-ray energy: 8 keV
Control of coherence is important!


Stony Meteorite Allende 8 keV , x7.61, BM3(x10), voxel size $0.13 \mu \mathrm{~m}$.
 100 projection, exposure time: $15 \mathrm{~s} /$ projection.

Diatom "Achnanthidium lanceolata" $8 \mathrm{keV}, \mathrm{x10}$, BM3(x10), voxel size $0.1 \mu \mathrm{~m}$. 360 projection, exposure time: $\mathbf{6 0} \mathrm{s} /$ projection.

## X-ray Micro-tomography using Imaging Optics with Fresnel Zone Plate Objective

Low-emittance SR source is not suitable for imaging microscopy, because of
high spatial coherence:
Small source size ( $\sim 10 \mu \mathrm{~m}$ vertical $\times 100 \mu \mathrm{~m}$ horizontal), Small divergent angle ( $\sim 10 \mu \mathrm{rad}$ ).

Critical illumination with simple condenser lens:
F-number matching --> small field of view (<a few $\mu \mathrm{m}$ ), Coherent illumination --> Speckle noise.

Critical illumination and Köhler illumination
(best optics for imaging microscopy)

Critical illumination:
Demagnified image of source at the object plane., Each point of source corresponds to each point of field of view, Not suitable for 3rd generation SR source.

Köhler's illumination:
Infinite focus,
Each points at source to each angle of illuminating beam.

## Illumination Optics for Imaging Microscopy

First experiment on imaging microscopy at SPring-8:
Parallel beam illumination
--> Edge-enhancement artifact,
Strong speckle noise.
2nd Step:

Partial Coherent illumination by diffuser
--> Less artifacts, and no speckles, Weak edge-enhancement, Nonuniform imaging properties in the field of view, Asymmetric feature of imaging properties. (off-axial illumination)

Need of Condenser Optics for Imaging microscopy.

Rayleigh's criterion (incoherent condition) [uncertainty principle in quantum physics]

$$
\Delta=0.61 \lambda / N A
$$



Parallel beam illumination:

$$
\Delta=0.82 \lambda / N A
$$

$N A$ : numerical aperture of objective lens.
With condenser optics of 1.5NA:

$$
\Delta=0.57 \lambda / N A
$$

$$
N A=\sin \theta
$$

Useful formula:

$$
\Delta=1.22 d r_{\mathrm{N}}
$$

$d r_{\mathrm{N}}$ : Outermost zone width

$$
\begin{aligned}
& \text { Example: } \\
& d r_{\mathrm{N}}=100 \mathrm{~nm}, \\
& \Delta=122 \mathrm{~nm} . \\
& N A=7.75 \times 10^{-4} \text { at } 8 \mathrm{keV} . \\
& (8 \mathrm{keV}=1.55 \AA)
\end{aligned}
$$

## Spatial Resolution of FZP Microscope

Geometrical defocusing:

$$
2 D \times N A
$$



Limit of defocusing:
Diffraction-limited resolution $=$ Geometrical defocusing

$$
2 D \times N A=0.61 \lambda / N A,
$$

Depth of focus (tolerance of sample thickness):

$$
2 D=0.61 \lambda / N A 2 .
$$

In tomography measurement,
Depth of focus > Sample diameter.

$$
\begin{aligned}
& \text { Example: } \\
& \Delta=122 \mathrm{~nm}\left(d r_{\mathrm{N}}=100 \mathrm{~nm}\right), \\
& N A
\end{aligned}=7.75 \times 10^{-4} \text { at } 8 \mathrm{keV} .
$$

## Depth of Focus



Second order approximation and the Rayleigh's quarter wavelength rule:
$\mid\left\{-r_{\mathrm{a}} r_{\mathrm{n}} \cos \phi / a+r_{\mathrm{b}} r_{\mathrm{n}} \cos \phi / b\right\}+1 / 2\left\{r_{\mathrm{n}}{ }^{2} / a+r_{\mathrm{n}}{ }^{2} / b-n \lambda\right\}$
$-1 / 8\left\{\left(r_{\mathrm{a}}^{2}-2 r_{\mathrm{a}} r_{\mathrm{n}} \cos \phi+r_{\mathrm{n}}^{2}\right)^{\left.2 / a^{3}-r_{\mathrm{a}}^{4} / a^{3}+\left(r_{\mathrm{b}}^{2}+2 r_{\mathrm{b}} r_{\mathrm{n}} \cos \phi+r_{\mathrm{n}}^{2}\right)^{2 / b^{3}}-r_{\mathrm{b}}^{4} / b^{3}\right\} \mid<\lambda / 4 .}\right.$

## Aberration Theory of FZP Microscope by Wave Optics

Depth of focus (tolerance of sample thickness for tomography):

$$
\begin{aligned}
& 2 D=0.61 \lambda / N A^{2}, \\
& N A \sim r_{\mathrm{N}} / f, D \sim r_{\mathrm{a}} \quad-\cdots \quad r_{\mathrm{a}} r_{\mathrm{N}}^{2} / f^{2}<0.3 \lambda \\
& r_{\mathrm{N}} / f \ll 1, r_{\mathrm{a}} / f \ll 1 \text { for hard -X-ray FZP. }
\end{aligned}
$$

Other wavefront aberrations:

$$
\begin{aligned}
& 3 r_{\mathrm{a}}^{2} r_{\mathrm{N}}{ }^{2} / f^{3}<\lambda, \\
& 2 r_{a_{\mathrm{N}}} r^{3} / f^{3}<\lambda, \\
& 1 / 2 r_{\mathrm{N}} / f^{3}<\lambda
\end{aligned}
$$

Chromatic aberration:

$$
\Delta \lambda / \lambda<0.61 / N,(N: \text { total zone number }) .
$$

$\Delta \lambda / \lambda \sim 10^{-4}$ (crystal monochromator, Si 111)

$$
\begin{aligned}
& \text { Example: } \\
& f=100 \mathrm{~mm} \text { at } 8 \mathrm{keV}, \\
& r_{\mathrm{N}}=77.5 \mu \mathrm{~m}, \\
& N=388, \\
& N A=7.75 \times 10^{-4} \text { at } 8 \mathrm{keV} . \\
& \quad(\lambda=1.55 \AA) \\
& M \sim 70
\end{aligned}
$$

Most serious aberration is Depth of Focus!


Hard X-ray Imaging Micro-tomography

Fresnel zone plate $=$ Chromatic aberration,
Requirement on monochromaticity for Fresnel zone plate $\sim$ Number of Fresnel zone.
---> $\Delta \lambda / \lambda<1 / \mathrm{N}$ (number of Fresnel zone)
$\mathbf{N} \sim$ or $>100$, (requirement for natural lens approximation).

$$
\begin{aligned}
& \Delta \lambda / \lambda \sim 10^{-4} \text { with crystal monochromator, } \\
& \text { too narrow! ---> loss of photon flux. } \\
& \text { Use of direct undulator radiation, } \\
& \Delta \lambda / \lambda \sim 100 \text {. } \\
& --->\text { High flux microbeam, } \\
& \text { Short Exposure Time. }
\end{aligned}
$$

BL40XU of SPring-8 (High Flux Beamline)

1. Undulator radiation without monochromator, $\Delta \lambda / \lambda \sim 1.2 \%$ @ $\varepsilon=3 \mathrm{~nm} \mathrm{rad}$
2. Helical Undulator --> Suppression of higher order,
3. Condenser Optics: K-B mirror


Measured Spectra of Undulator Radiation Front-end Slit Aperture:
$15 \mu \mathrm{rad}$ (horizontally) x $5 \mu \mathrm{rad}$ (vertically)
Available flux $\boldsymbol{\sim} \mathbf{1 0 0}$ times that at conventional beamlines (undulator beamlines with crystal monochromator.

X-ray Microbeam \& Imaging Microscopy with Sub-micron resolution and high flux! ( $\sim 100$ times, compared with conventional beamlines)


## Experimental Setup for Imaging Microscopy at BL40XU SPring-8



Object: Cu mesh, 2000 lines/inch
$10 \mu \mathrm{~m}$


Object: Fresnel zone plate, $0.25 \mu \mathrm{~m}$ outermost zone width

Image of test object
Objective: FZP, $0.25 \mu \mathrm{~m}$ outermost zone width, 100 zones, Magnification: 11.3, X-ray energy: 8.34 keV , Exposure time: 1.5 ms (Single Shot)

Hard X-ray Imaging Microscopy with Fresnel Zone Plate Objective \& Quasi-monochromatic Undulator Radiation at BL40XU


# Optical Layout of Microbeam Experiment at BL40XU of SPring-8 



Measured Profiles of Focused Beam

X-ray Energy: 8.317 keV
Total Flux of Focused Beam:
$\sim 2 \times 10{ }^{12}$ photons/s

$151 \times 334$ pixels,
$0.3 \mu \mathrm{~m} / \mathrm{pixel}$,
0.3 s dwell time.
$66 \times 126$ pixels, $0.2 \mu \mathrm{~m} / \mathrm{pixel}$, 0.2 s dwell time.

Scanning Microscopic Images of Resolution Test Patterns

Microbeam and Scanning Microscopy with FZP and Quasi-monochromatic Undulator Radiation

Slit or Pinhole
Monochromator (10-100 $\mu \mathrm{m}$ )


Experimental Setup of X-ray Microbeam/Scanning Microscopy with Total-reflection Mirror Optics (Kirkpatrick-Baez Configuration)

Kirkpatrick-Baez Optics with Aspherical (Plane Parabola) Mirrors, L1: $\mathbf{4 5} \mathrm{mm}$, L2: $\mathbf{4 5} \mathrm{mm}$, L3: $\mathbf{2 5} \mathrm{mm}, f: \mathbf{7 5} \mathrm{mm}$, Glancing angle: $\mathbf{2 . 8} \mathbf{~ m r a d}$. (Pt coated $\mathrm{SiO}_{2}$ ), Fabricated at Cannon Co. Japan.


Focused Beam Profiles measured by Knife-edge Scan

Scanning Microscopy Image of Test Patterns $0.1 \mu \mathrm{~m}$ line\&space X-ray Energy: 12 keV

## Micirobeam and Scanning Microscopy with Total-reflection Mirror Optics

- Measured data (FWHM)
- Diffraction limit
$\therefore$ - Geometrical Size



Energy Dependence of Resolution


Pt surface,
Glancing angle: 2.8 mrad.

Design Parameters of Parabolic Mirrors


Total Reflection Mirror for High Energy X-ray Microbeam


## Total Reflection Mirror for High Energy X-ray Microbeam




Fabrication Process of Sputtered-sliced Fresnel Zone Plates


## SEM Image of Sputtered-sliced Fresnel Zone Plate

Au Core ( $50 \mu \mathrm{~m}$ in diameter), Cu/Al 50 Layers, Outermost zone width of $0.15 \mu \mathrm{~m}$.


X-ray wavelength: $1.4 \AA(8.9 \mathrm{keV})$, f $\sim 158 \mathrm{~mm}$,
$\mathrm{Cu} / \mathrm{Al}$ sputtered-sliced FZP ( 50 layers), Core (beam stop): Au $50 \mu \mathrm{~m}$ in diameter, Outermost zone width: $0.25 \mu \mathrm{~m}$, Thickness: ~ $\mathbf{2 0} \boldsymbol{\mu} \mathrm{m}$.
Diffraction efficiency: 25\% @ $1.4 \AA$

X-ray wavelength: $0.5 \AA$ ( 24.8 keV ), $\mathrm{f} \sim \mathbf{2 2 0} \mathrm{mm}$, $\mathrm{Cu} / \mathrm{Al}$ sputtered-sliced FZP (70 layers), Core (beam stop): Au $100 \mu \mathrm{~m}$ in diameter, Outermost zone width: $0.09 \mu \mathrm{~m}$, Thickness: $\sim \mathbf{~ 6 0 ~} \boldsymbol{\mathrm { m }}$.
Sagittal Focus (1/4 of annular aperture)

Focused Beam Profile Measured by Edge-scan @BL20XU


Diffraction efficiency of Fresnel zone plate (first order) Cu/Al Sputtered-Sliced FZP, Thickness: ~20 $\mu \mathrm{m}$.
Core: Gold, $50 \mu \mathrm{~m}$ in diameter, 50 layers.


Calculated diffraction efficiency of Fresnel zone plate
$\mathrm{Cu} / \mathrm{Al}$ multilayer
Thickness: $\mathbf{2 0} \boldsymbol{\mu \mathrm { m }}$

$0.3 \mu \mathrm{~m}$ line \& space
$0.2 \mu \mathrm{~m}$ line \& space
X-ray wavelength: 1.4 Å, $128 \times 64$ pixels, $0.0625 \mu \mathrm{~m} / \mathrm{pixel}$, Dwell time: $0.4 \mathrm{~s} /$ pixel.

$0.1 \mu \mathrm{~m}$ line $\&$ space
X-ray wavelength: 1.0 Å, $256 \times 70$ pixel, $0.0625 \mu \mathrm{~m} / \mathrm{pixels}$, Dwell time: $\mathbf{0 . 4} \mathbf{~ s} /$ pixel.

Scanning Microscopic Image of Resolution Test Pattern


Microfocusing/scanning microscopy with SS-FZP at 82 keV


## Microbeam with Sputtered-sliced FZP

## Focused Beam Profile Measured by Edge-scan @BL20XU

X-ray wavelength: $0.124 \AA(100 \mathrm{keV}), \mathrm{f} \sim 900 \mathrm{~mm}$, $\mathrm{Cu} / \mathrm{Al}$ sputtered-sliced FZP (70 layers), Core (beam stop): Au $50 \mu \mathrm{~m}$ in diameter, Outermost zone width: $0.16 \mu \mathrm{~m}$, Thickness: ~ $\mathbf{1 8 0} \boldsymbol{\mu} \mathrm{m}$.

## Resolution Limit of X-ray Microscope

## General Theory <br> Rayleigh's criterion (Diffraction Limit in Classical Optics)

$\delta ; \mathbf{C} \lambda / \mathrm{NA}$,

$\mathbf{N A}=\mathbf{n} \sin \theta$,
n: Index of Refraction,
C ~ 1 (constant, dependent on optics configuration).

Typically, $\mathrm{C} \sim 0.61$ (Circular aperture), $\mathrm{n} \sim 1$ (in air), $\sin \theta \sim 0.5$ ( $\mathrm{F} \sim 1$ ) for visible light
$\delta \sim \lambda$ : Resolution limit of Optical Microscope.

## General Theory

## Uncertainty Principle (Quantum Mechanics)

$$
\Delta \mathrm{p} \Delta \mathrm{x} \geq h
$$

Momentum of Photon: $\boldsymbol{h} \boldsymbol{\lambda}$
Momentum Spread by Focusing Optics: $\Delta \mathrm{p}=2|\mathrm{p}| \sin \theta$


$$
\Delta Y \geq \lambda /(2 \sin \theta)
$$

How about hard X-ray microscopy?

## Total Reflection Mirror Optics

Elliptical Mirror Optics:
NAmax $=\mathbf{2 \theta c}$

$$
\Delta x \geq 0.61 \times \lambda /(2 \theta c)
$$



Using free-electron approximation,

$$
\begin{equation*}
\theta c(\mathrm{rad}) \sim 1.6 \times 10^{-2} \lambda \rho 1 / 2 \tag{3}
\end{equation*}
$$

$\rho(\mathrm{g} / \mathrm{cm} 3)$ : Density of Mirror Material,
$\lambda$ (nm): X-ray wavelength.

The theoretical limit of spatial resolution, $\Delta x$, is determined only by the density of the reflector surface material, $\sqrt{\rho}$.
The limit of spatial resolution is approximately 10 nm .

For combined mirror optics
(Wolter-type-mirror or tandem-toroidal-mirror optics),

$$
\begin{equation*}
\Delta x=0.61 \times \lambda /(4 \theta c) \tag{4}
\end{equation*}
$$

1. P. Kirkpatrick and A. V. Baez: J. Opt. Soc. Am. 38 (1948) 766.
2. Von H. Wolter: Ann. Physik 10 (1952) 94.
3. Y. Sakayanagi: Optica Acta 23 (1976) 217.

## X-ray Wave Guide

Planar wave guide, 1-D solution,

Boundary Condition: $2 \mathrm{~d} \sin \theta=\mathrm{m} \lambda, \mathrm{m}=1,2,3, \ldots .$.

Lowest mode of propagating wave: $\mathbf{m}=1$,
$d \sin \theta=\lambda / 2$,
d: gap of waveguide (inner diameter of waveguide)
$\theta$ : glancing angle to wall


When the phase jump at total reflection $=\pi$ (case of $\theta \ll \theta c$ ), minimum size of wave guide, do, $d o=\lambda /(2 \theta) \leq \lambda /(2 \theta c)$.

However, the penetration depth of evanescent wave, $t$,
$t \sim \lambda /\left(\theta c^{2}-\theta^{2}\right)^{1 / 2}$. So, effective broadening of wavepacket is
$\Delta \mathrm{x} \sim \mathrm{t} \sim \lambda / \theta \mathrm{c}$ : the same as that of total reflection mirror optics.
or $\Delta x \leq \lambda /(2 \theta c)$, simply from uncertainty principle.
cf. C. Bergemann, H. Keymeulen and J. F. van der Veen: Phys. Rev. Lett. 91 (2003) 204801.

## Numerical Calculation of Wave-packet in Wave-guide




Electric Field Intensity in the Wave-guide

$$
\begin{aligned}
& \text { Si }(\rho=2.34), \lambda=1.28 \AA, \\
& d=60 \AA, \text { and } d=160 \AA .
\end{aligned}
$$

## Refractive Lens Optics



Spherical Lens: Spherical Aberration

$$
\begin{equation*}
\left(x^{2}+y^{2}\right)^{1 / 2}+n(f-x)=f \tag{6}
\end{equation*}
$$

n : index for refraction


Refractive Lens: Exact Solution

## Diffraction-limited Resolution of Single Refractive Lens

Considering phase shit of $2 m \pi$, $(m \lambda, m=1,2,3, \ldots$.
$\left(\mathbf{x}^{2}+\mathbf{y}^{2}\right)^{1 / 2}+\mathbf{n}(f-\mathrm{x})=f+\mathbf{m} \boldsymbol{\lambda}$,
(8)
$[x-\{f+m \lambda /(1-n)\} n /(1+n)]^{2} /\left[\{f+m \lambda /(1-n)\}^{2} /(1+n)^{2}\right]+\mathbf{y}^{2} /\left[\{f+m \lambda /(1-n)\}^{2}(1-n) /(1+n)\right]=1 . \quad$ (9)
Numerical Aperture of the Lens (NA):
NAmax $=[(1-n) /(1+n)]^{1 / 2} /[1 /(1+n)]=\left(1-n^{2}\right)^{1 / 2}$.
Using $\mathrm{n}=1-\delta$, and $\delta \ll 1$,

$$
\begin{aligned}
& \text { NAmax } \sim(2 \delta)^{1 / 2} . \\
& \theta c \sim(2 \delta)^{1 / 2} . \\
& \Delta=0.61 \times \lambda / \theta c .
\end{aligned}
$$


cf. Y. Suzuki, Jpn. J. Appl. Phys. 43 (2004) 7311-7314.

## Expansion to Fresnel Lens and Fresnel Zone Plate

The nesting configuration, the series of ellipsoids $\mathbf{m}=0,1,2,3,,,, M$
Fresnel zone plate at $f=\mathrm{x}$ :

$$
\begin{align*}
& \left(f^{2}+\mathrm{y}^{2}\right)^{1 / 2}=f+\mathrm{m} \lambda  \tag{14}\\
& \mathrm{y}=\left[2 \mathrm{~m} \lambda f+(\mathrm{m} \lambda)^{2}\right]^{1 / 2} \tag{15}
\end{align*}
$$

When $f \gg \mathrm{~m} \lambda$, by neglecting the higher-order terms,

$$
\begin{equation*}
\mathrm{y}=(2 \mathrm{~m} \lambda f)^{1 / 2} . \quad[\text { Zone Plate Equation] } \tag{16}
\end{equation*}
$$

The major axis of the ellipse: $\{f+m \lambda /(1-n)\} /(1+n)$,
The major axis of the ellipsoid for the outermost zone should be smaller than the focal length $f$.

$$
\{f+\mathrm{m} \lambda /(1-\mathrm{n})\} /(1+\mathrm{n}) \leq f
$$

The possible outermost zone for the planar zone plate:

$$
\begin{aligned}
& \{f+\mathbf{M} \lambda /(1-\mathbf{n})\} /(1+\mathbf{n})=f . \\
& \mathbf{M}: \text { the maximum m. } \\
& \begin{aligned}
& \mathbf{M} \lambda /(\mathbf{1}-\mathbf{n})= \mathbf{n} f . \\
& \theta \max =(2 \mathrm{M} \lambda f)^{1 / 2} / f \\
&=\left[2 f^{2} \mathbf{n}(1-\mathrm{n})\right]^{1 / 2} / f \\
& \sim(2 \delta)^{1 / 2},
\end{aligned}
\end{aligned}
$$


cf. Y. Suzuki, Jpn. J. Appl. Phys. 43 (2004) 7311-7314.

## Theoretical Resolution Limit of Total Reflection Mirror Optics, Wave-Guide, Refractive Lens, Fresnel Zone Plate

$\sqrt{ }(2 \delta) \sim 10 \mathrm{~nm}$ in hard X-ray Region

## Possible Ways to Nanometer Resolution

1. Combined Refractive Lens,


## Diffraction Limited Resolution

$\sim 0.61 \times \lambda /(N \theta c)$
N : Number of Combined Lens

Spherical lens might be feasible,
because smaller lens has smaller aberration.
cf. C. Schroer and B. Lengeler, Phys. Rev. Let. 94 (2005) 054802

## Possible Ways to Nanometer Resolution

## 2. Three Dimensional Zone Plate (Volume Zone Plate or Laue Lens)



Nested Multilayer Structure of Ellipse of Rotation with Optical Path Difference of $m \lambda$.

Ideal only on Focusing Property.
H. C. Kang et al., Phys. Rev. Lett. 96 (2006) 127401,
C. Schroer, Phys. Rev. B 74 (2006) 033405.

Next limit: atom size with $\lambda / 4$ rule (Rayleigh limit)
$\sim 1 \mathrm{~nm}$.

## ERL \& FEL

Complementary?

Which is better for users?
Time structure \& spectral structure.
Nano-optics:
Applications? Users? Practical?
R\&D of optics: 10 nm resolution -> 1 nm resolution..?

Problems in the 3rd-generation SR source, Spring-8
Most of users and experiments are 2nd generation!

Important Problems in Coherent X-ray Sources

1. Vibration: optics, light source, ground\&building
2. Temperature stability: $\sim 0.01^{\circ}$ environment.
3. Radiation damages, cooling. Same as Spring-8?
4. Speckles:

No optics without any speckles.
5. No optics is best optics?

